

# Measurement of Buried Features in Packages Using 3D X-ray



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ZEISS Process Control Solutions

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# GAME CHANGER

## Advanced Packaging: Game Changer for Semiconductor Revolution

YOLE DEVELOPPEMENT April 4, 2019 Blogs, From Different Dimensions  
0 Comments

## Heterogeneous integration paving the way beyond silicon scaling limits

Reflections on IWLPC 2017

By Louis Burgyan, LTEC Corporation



As in prior years, the in-depth presentations at this year's IWLPC, covering a broad array of the industry's critical challenges, did not disappoint. A series of keynote presentations and papers included a couple of major announcements that will be discussed below. Of special note, several keynote speakers



## FOPLP at the verge of volume production

Over the years, the industry became accustomed to Apple being giving forward-looking and deep analysis can All the more reason t Planning Team at San

## Chip Industry Maps Heterogeneous Integration

Nicky Lu talks about 'ubiquitous intelligence'

## Advanced packaging to generate nearly US\$3 billion in revenues in 2019, says TSMC chairman

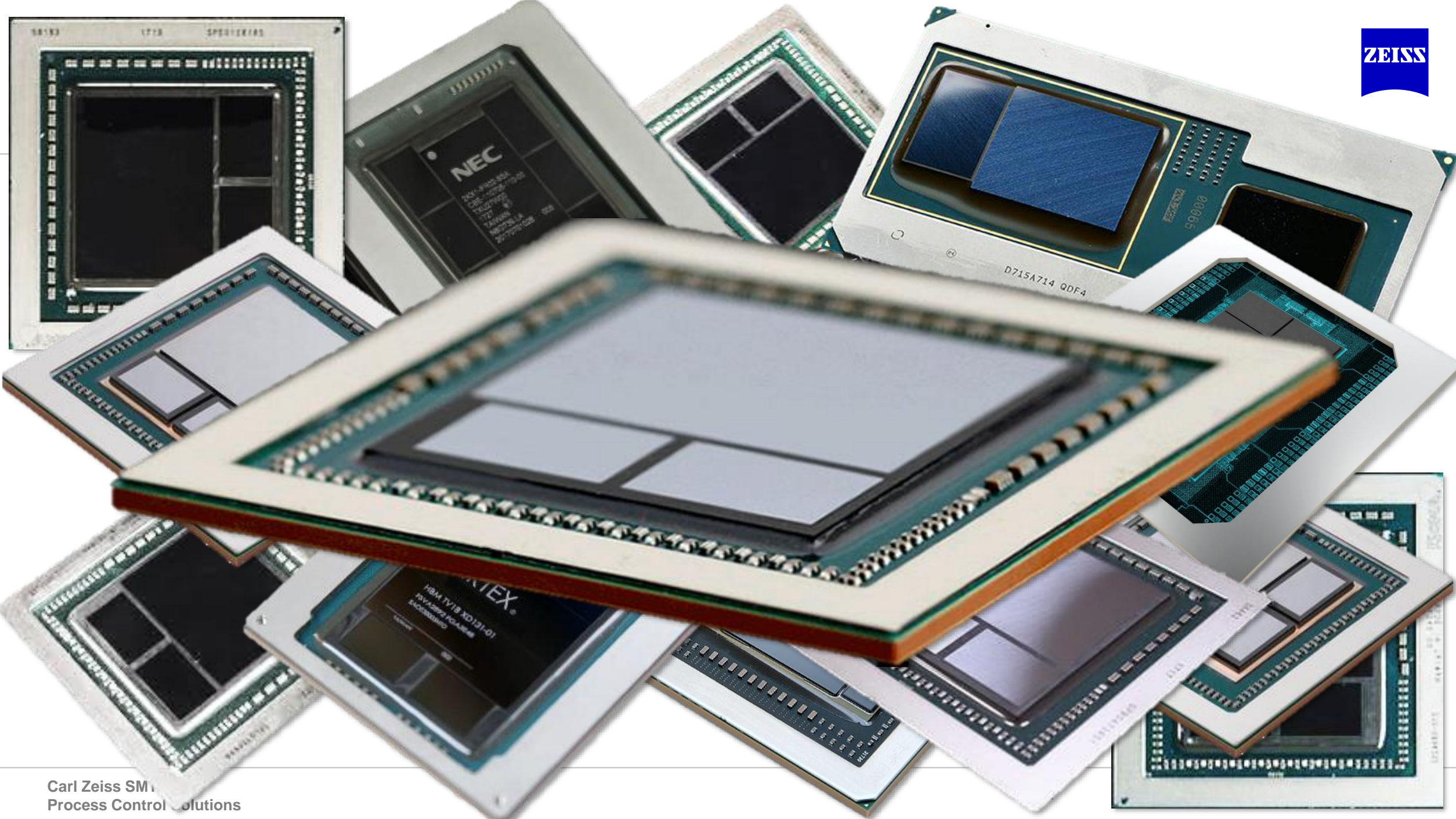
Julian Ho, Taipei; Willis Ke, DIGITIMES Tuesday 26 March 2019

Pure-play foundry TSMC remains aggressive in expanding its advanced packaging business, which will generate nearly US\$3 billion in revenues this year, according to company chairman Mark Liu.



Richard (Kwang Wook) B Samsung Electro-Mecha

rd global domination by way, we've seen that future, quality, and autonomous vehic





# Buried Costs!

# Buried Costs are not Directly Controllable

## Buried costs do not include:

- The bill of materials
- Direct labor
- Other directly controllable costs

## Buried package costs include:

- Process development costs incurred during the bring-up of a product
- The cost of line scrap and field failures when products do not meet performance requirements
- The cost of lost sales when products are not able to ship on-time



# There Might be a Few Gaps in Packaging Technology...



# Evolution of Semiconductor Inspection and Metrology



Wafer Fab



Package Asy



1970's~1980's

1980's~1990's

1990's~2000's

2000's~2010's

# Evolution of Semiconductor Inspection and Metrology



Wafer Fab



Package Asy



1970's~1980's

1980's~1990's

1990's~2000's

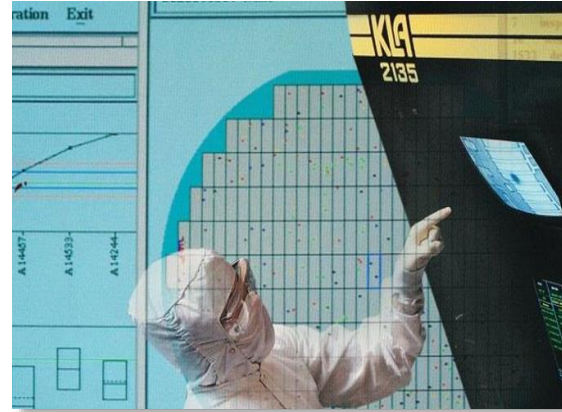
2000's~2010's



# Evolution of Semiconductor Inspection and Metrology



Wafer Fab



Package Asy



1970's~1980's

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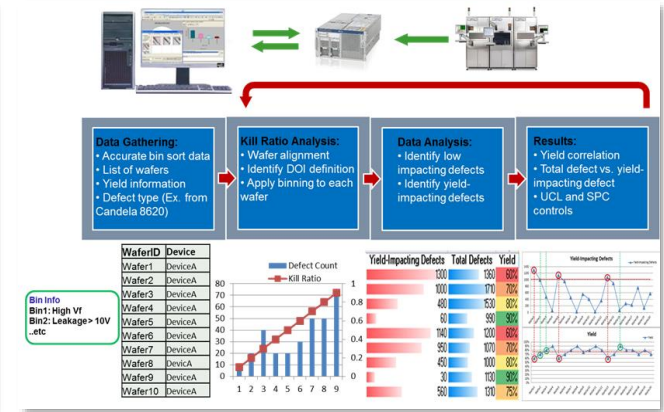
1990's~2000's

2000's~2010's

# Evolution of Semiconductor Inspection and Metrology



Wafer Fab



Package Asy



1970's~1980's

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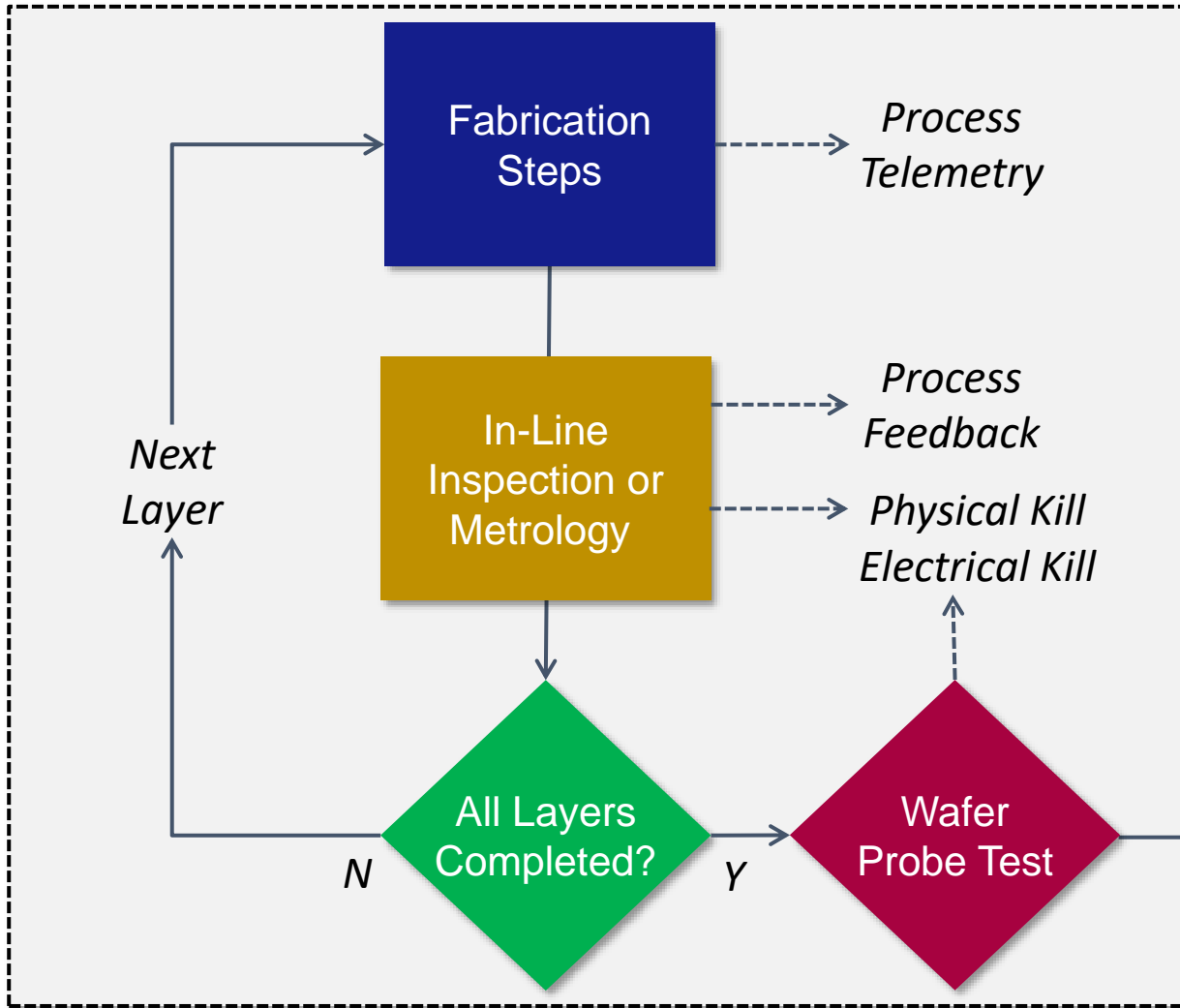
1990's~2000's

2000's~2010's

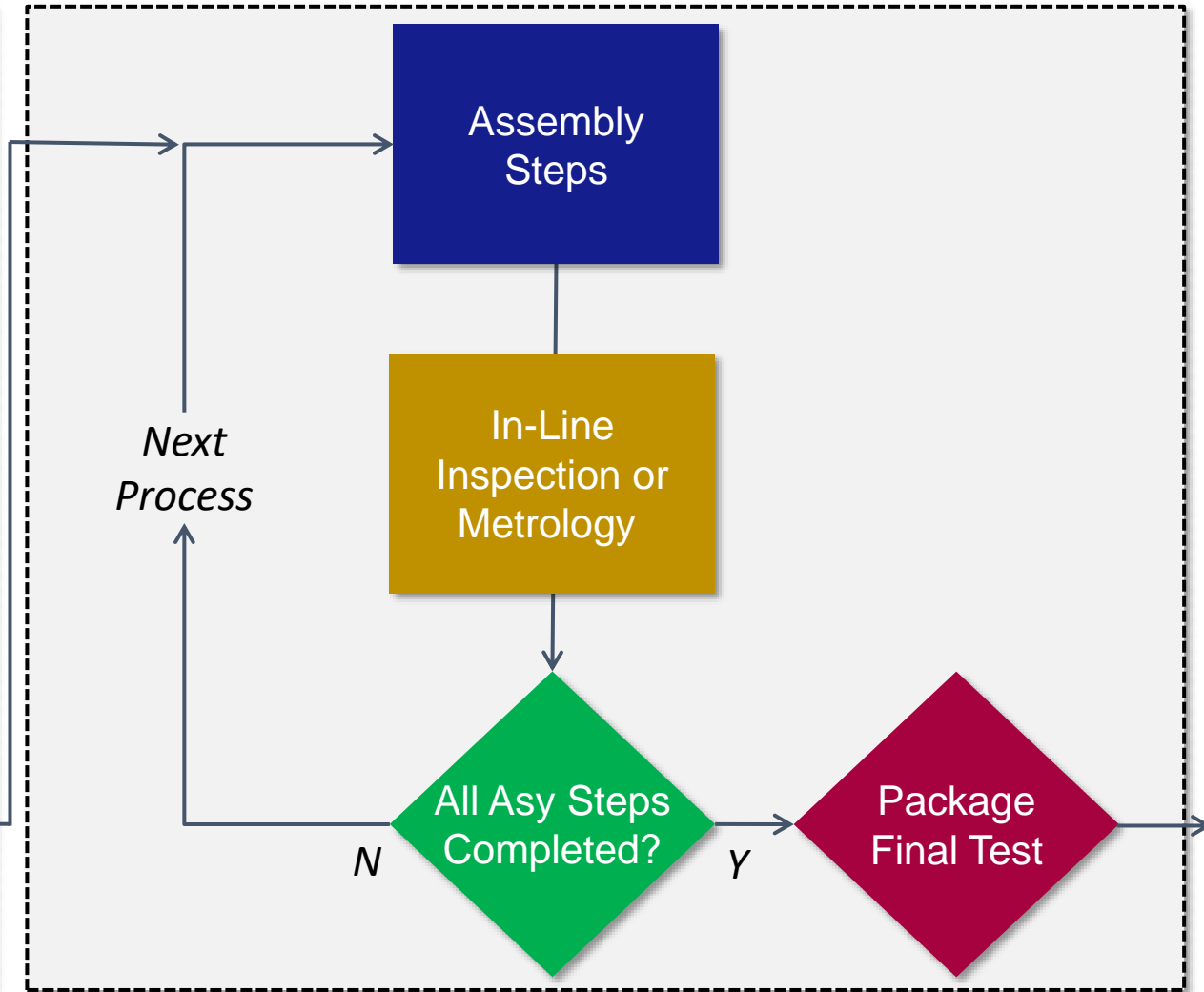
# Quality Systems Comparison



## Wafer Fabrication



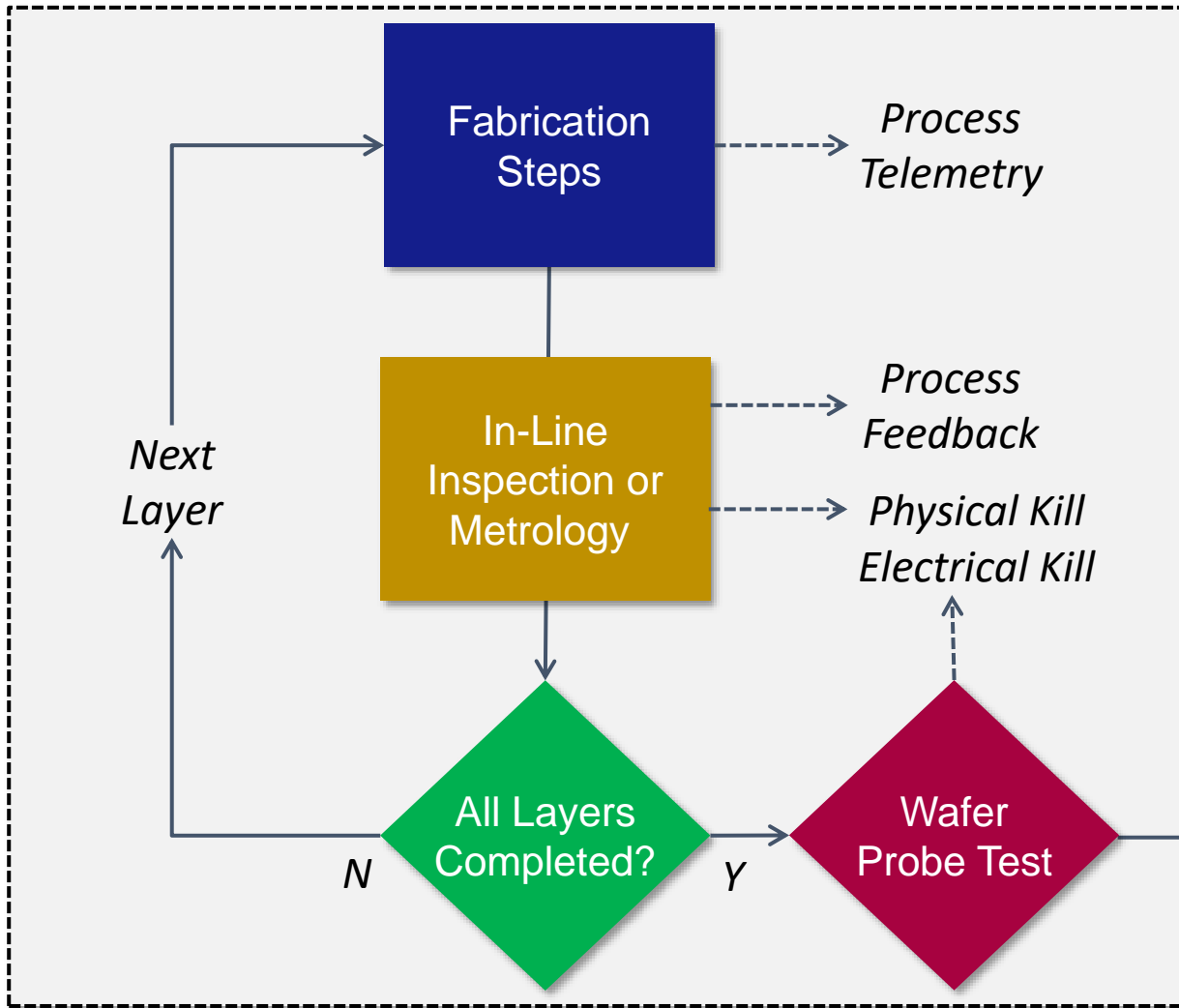
## Package Assembly



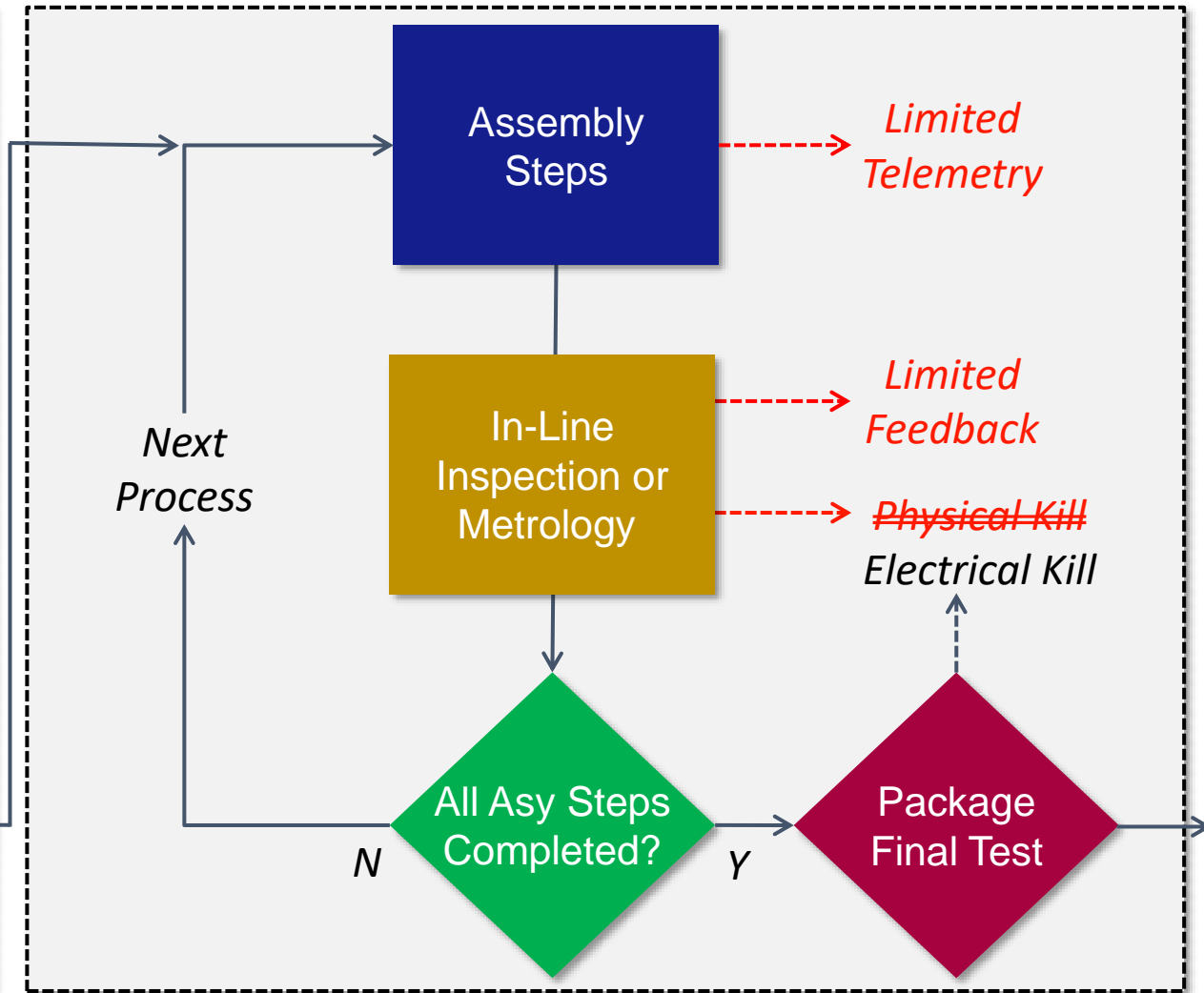
# Quality Systems Comparison



## Wafer Fabrication



## Package Assembly



# ZEISS 3D X-ray Solutions for Packaging



microCT  
(upgradeable  
to Versa)



**Context**

Next  
Generation  
Versa XRM



**600-series Versa**

Ultimate  
Nanoscale  
XRM



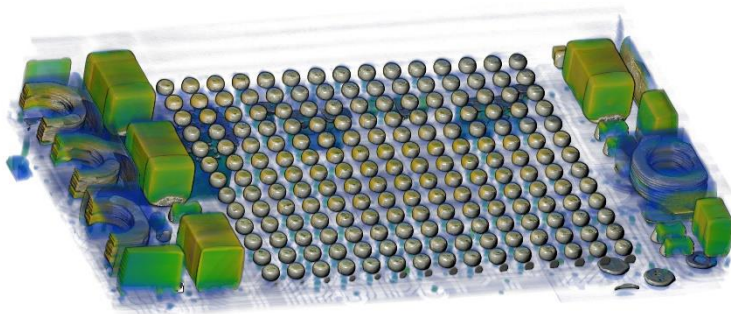
**800 Ultra**

Resolution:

950 nm

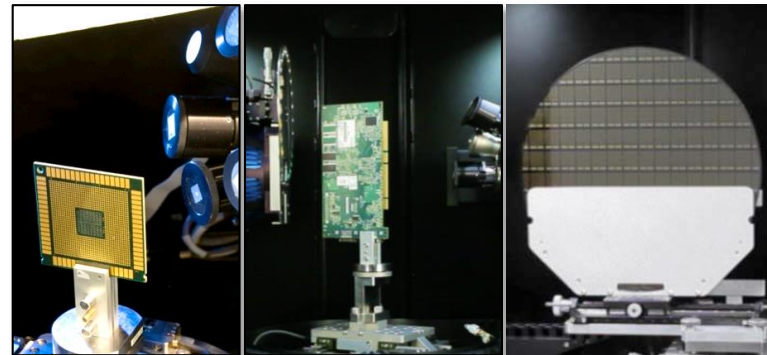
500 nm

150 nm, 50 nm

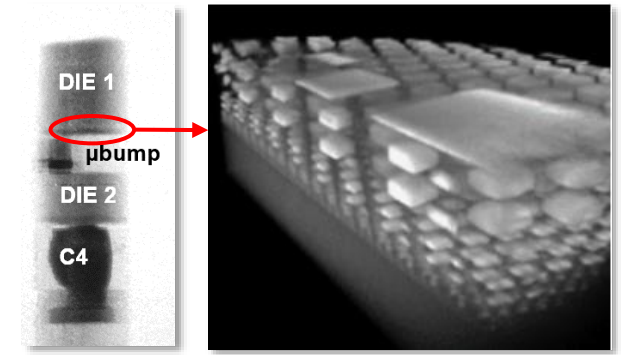


1 mm

Large field of view for all samples,  
high resolution for small samples

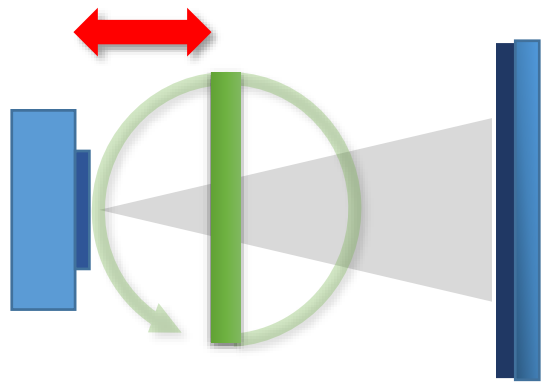


Versatile submicron 3D resolution  
on a variety of intact samples



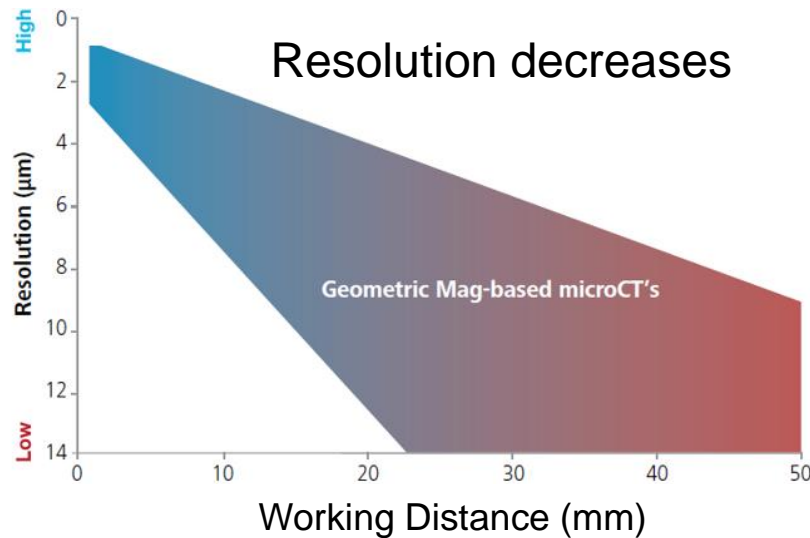
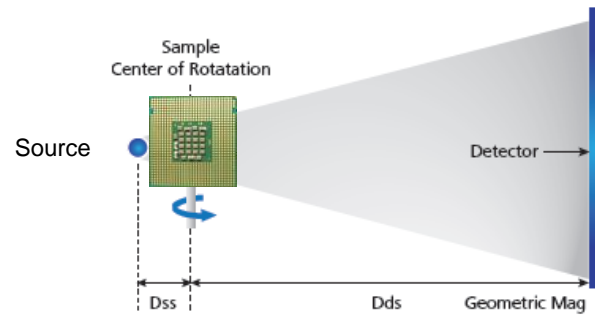
Nanoscale resolution for imaging  
ultra-fine pitch interconnects

# Versa X-ray Microscope vs. microCT

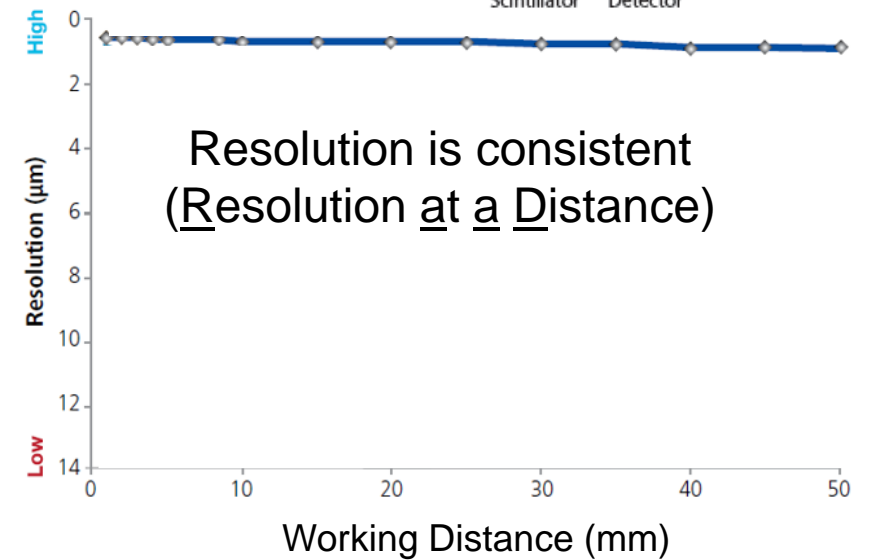
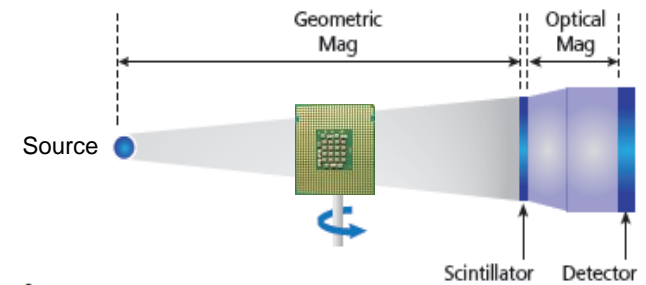


Working distance must increase as package body size increases

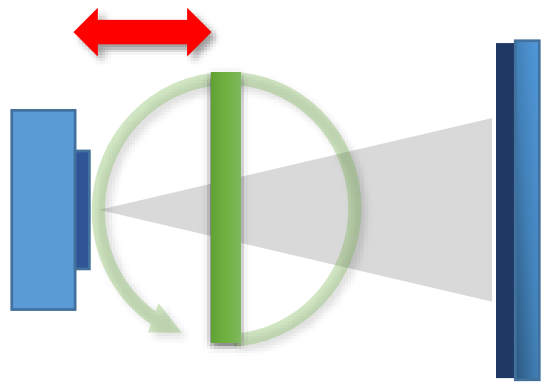
## microCT



## Versa XRM

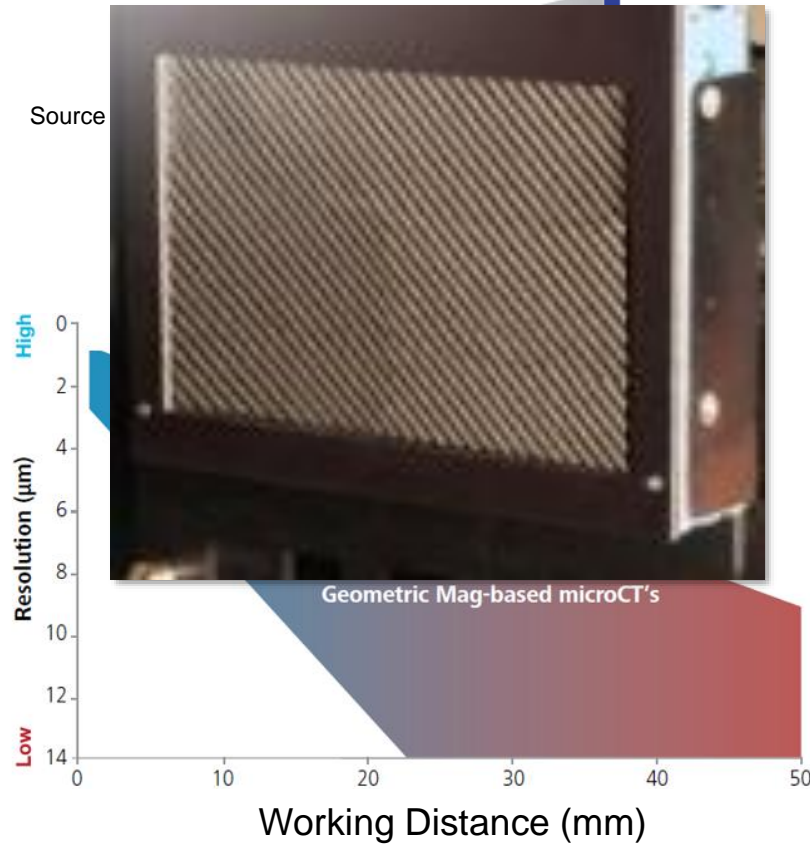


# Versa X-ray Microscope vs. microCT

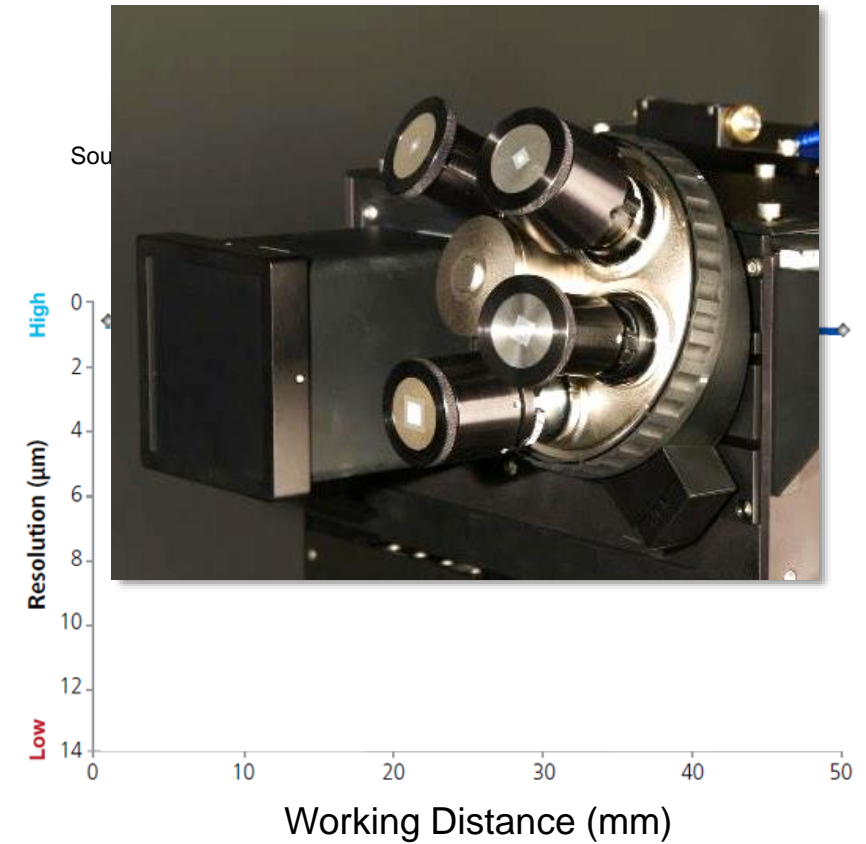


Working distance must increase as package body size increases

## microCT



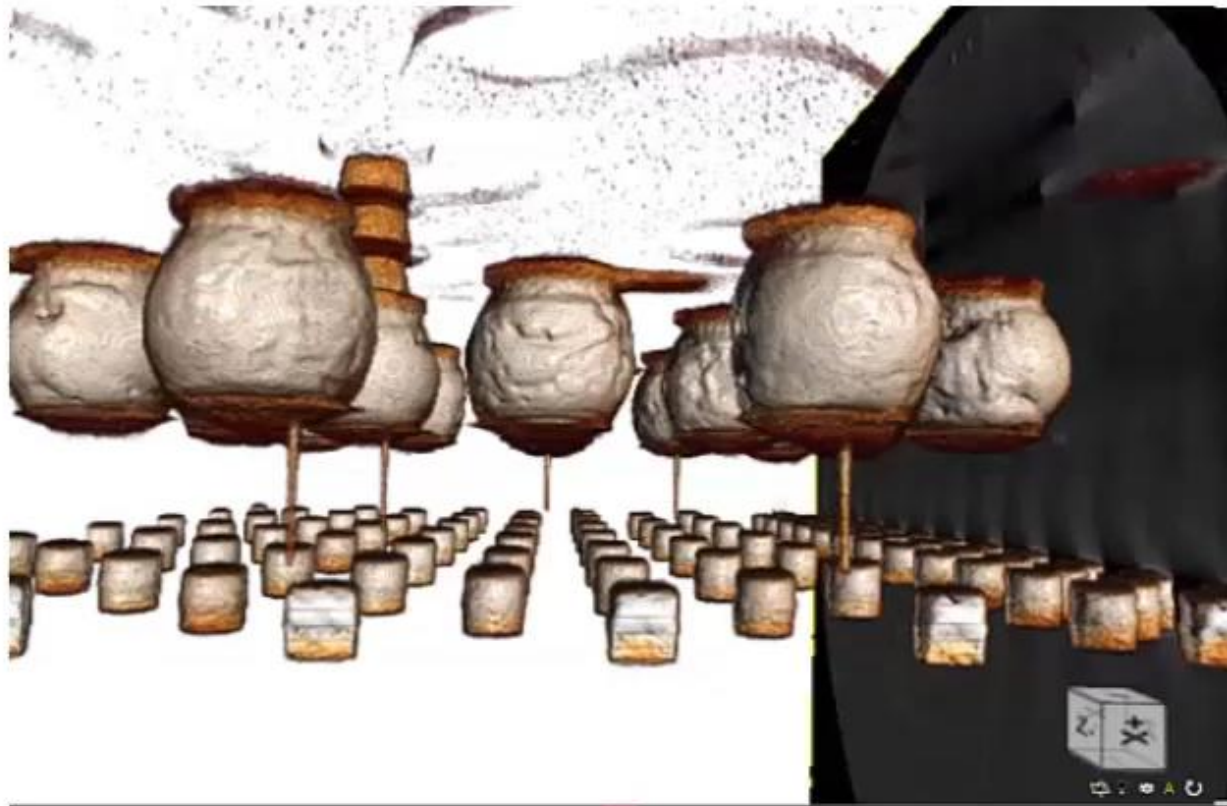
## Versa XRM



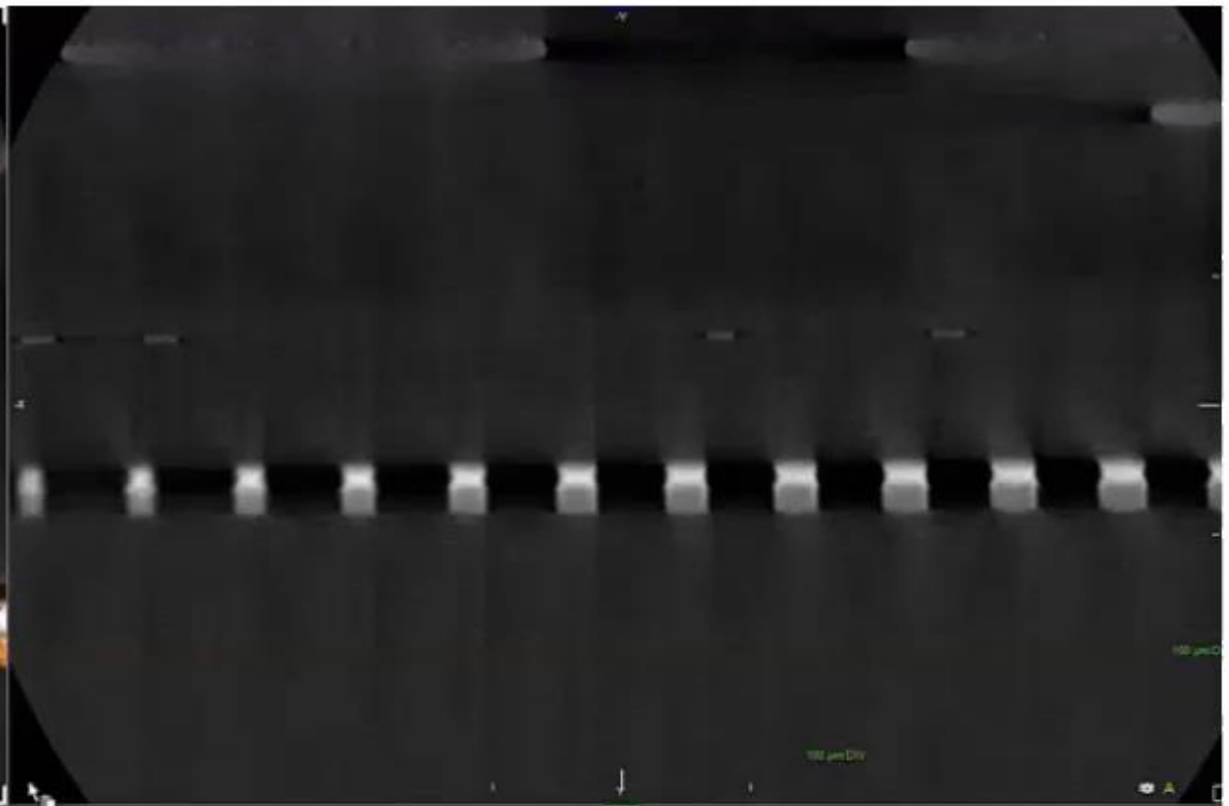
# Versa XRM 3D Dataset and Virtual Cross Section



## 3D Dataset

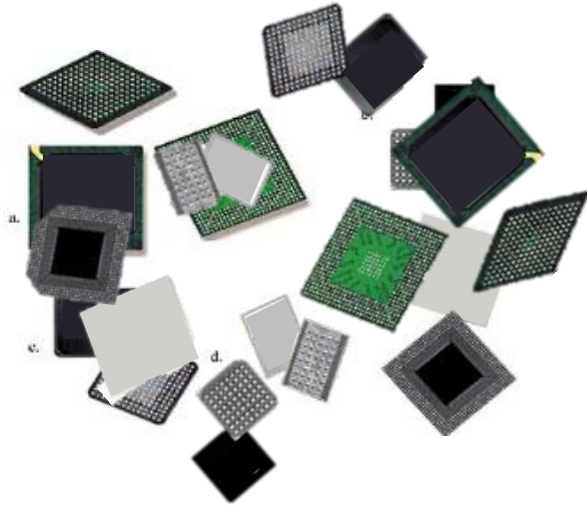


## Interactive Virtual Cross Section



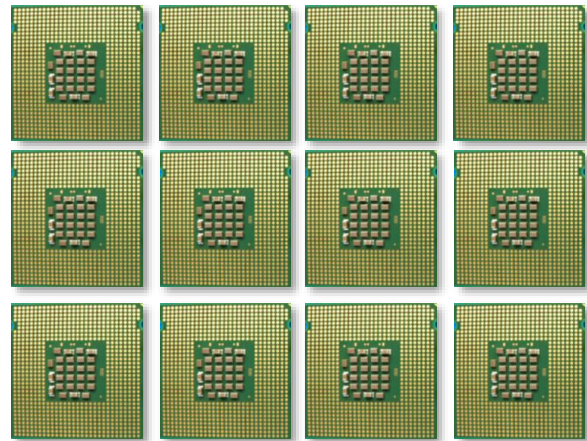
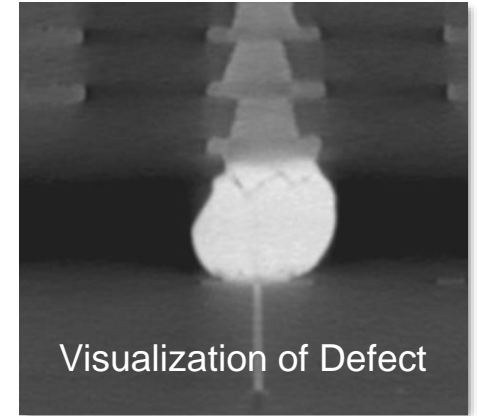


# Failure Analysis and Package Characterization



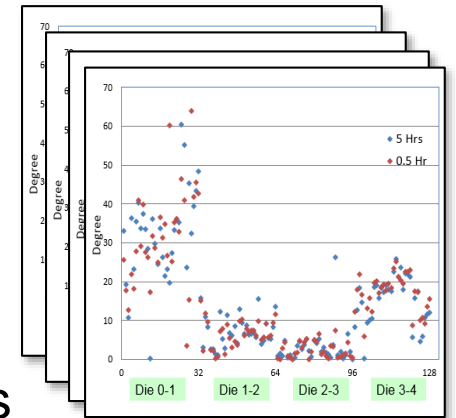
## Failure Analysis

- Root-cause analysis
- Usually 1~2 samples per job
- Each scan is unique
- Objective is defect visualization

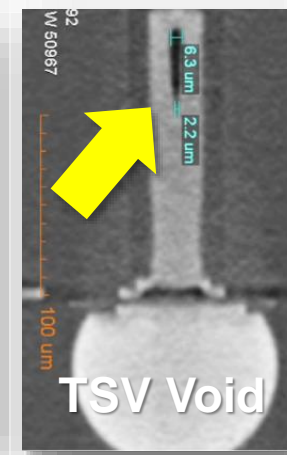
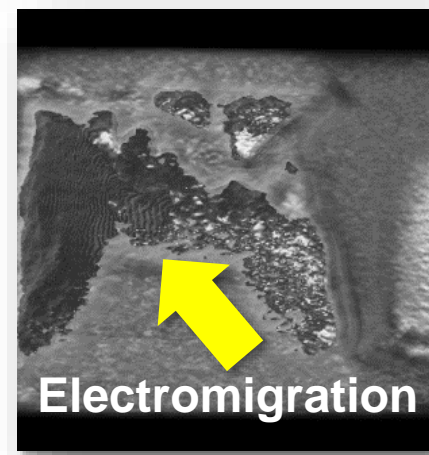
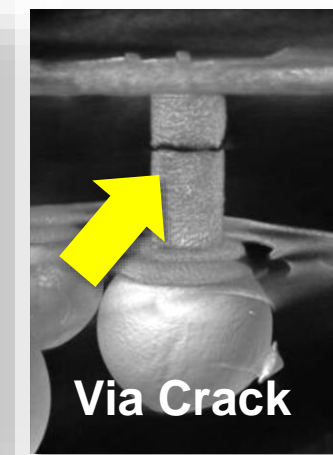
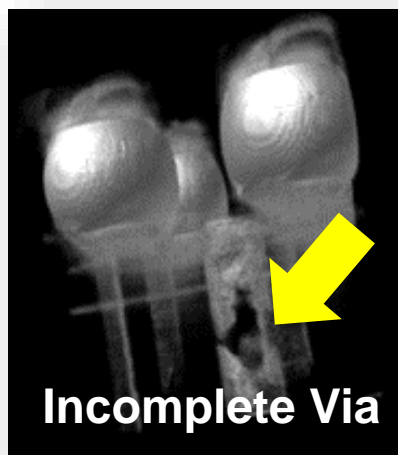
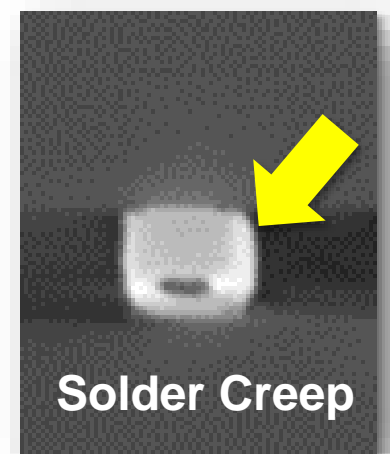
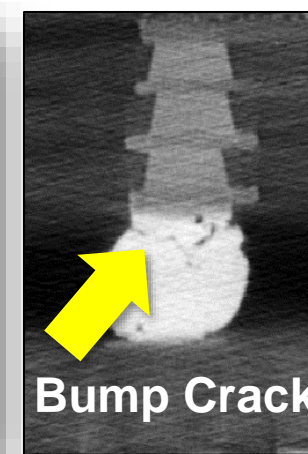
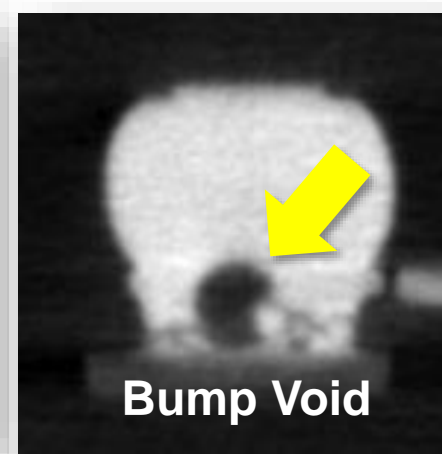
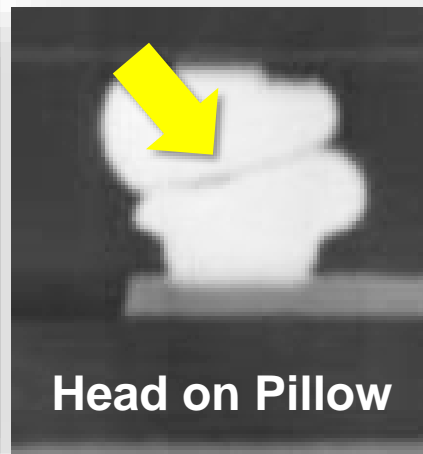
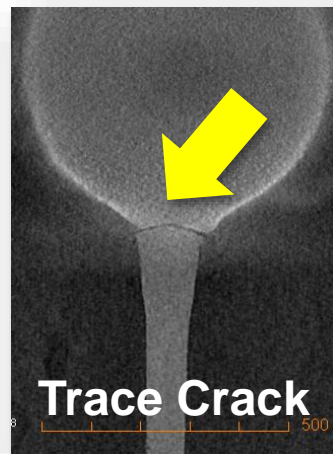
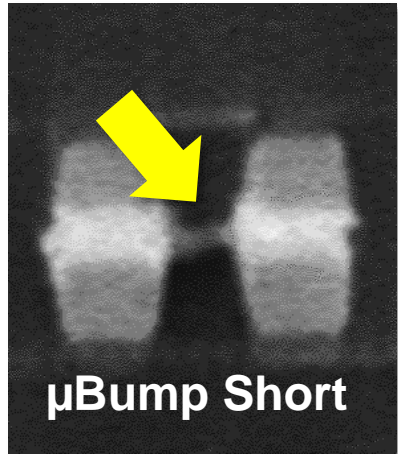


## Package Characterization

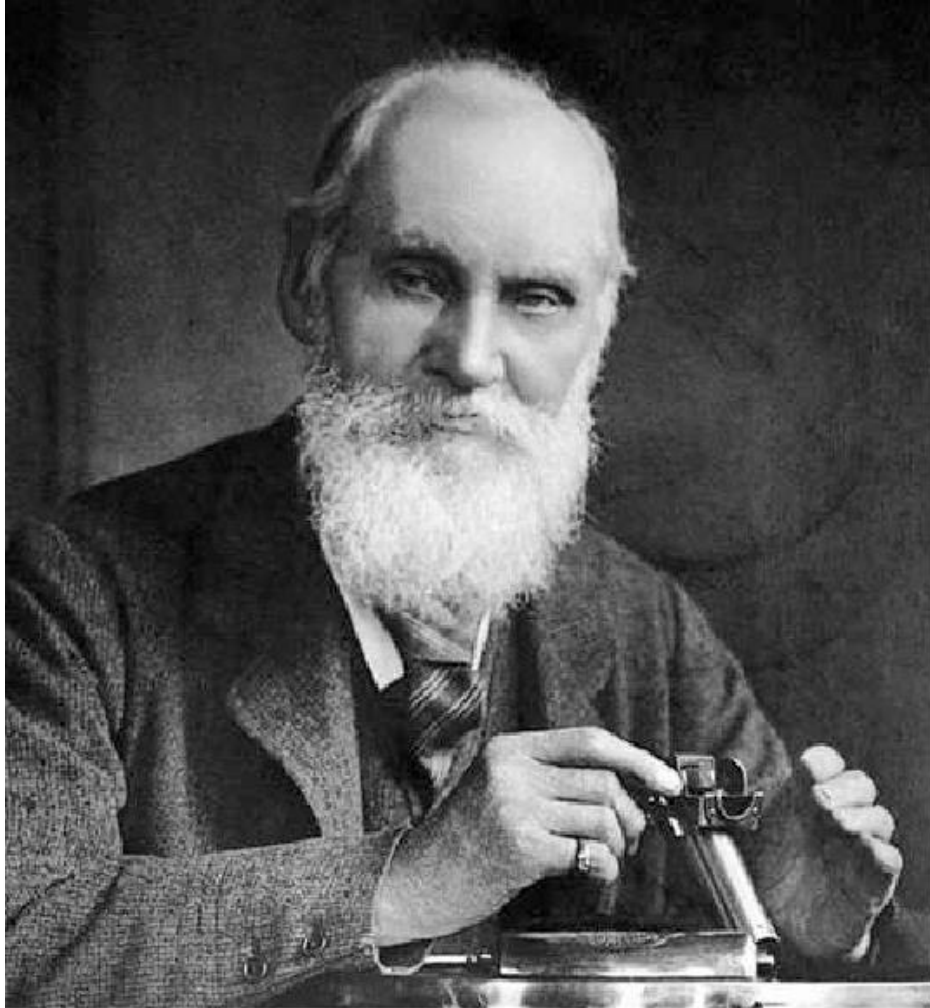
- Construction and process analysis
- Multiple samples per job (DOE's, etc.)
- Scans are often repeated
- Objective is measurement of critical parameters



# The Most Versatile 3D X-ray System in the Industry!



# Lord Kelvin (William Thomson)



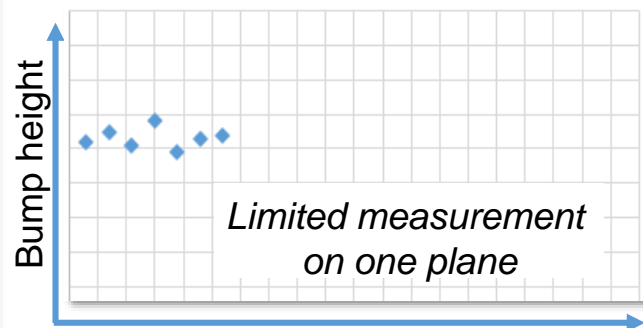
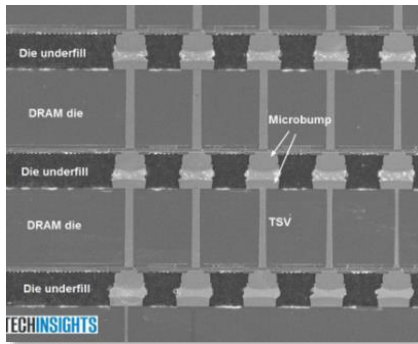
...when you can measure what you are speaking about, and express it in numbers, you know something about it...

Lecture on “Electrical Units of Measurement”, May 2, 1883

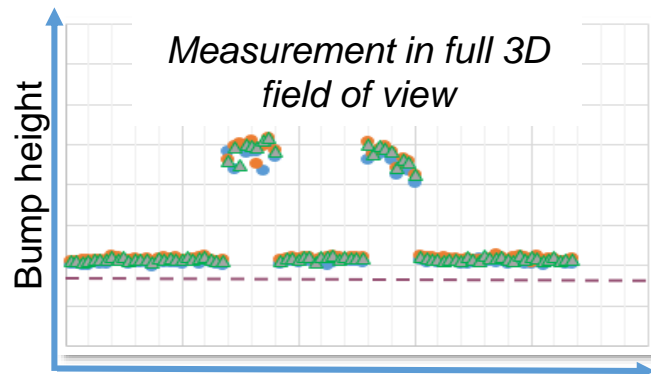
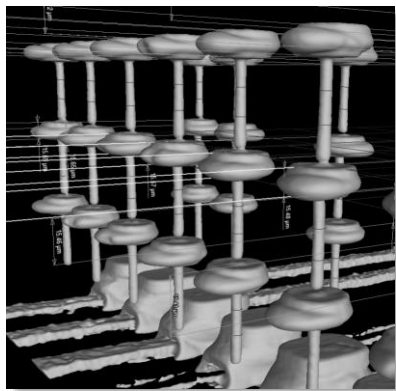
# 3D X-ray for Inspection and Measurement of Buried Features



## Physical Cross-Section Measurement

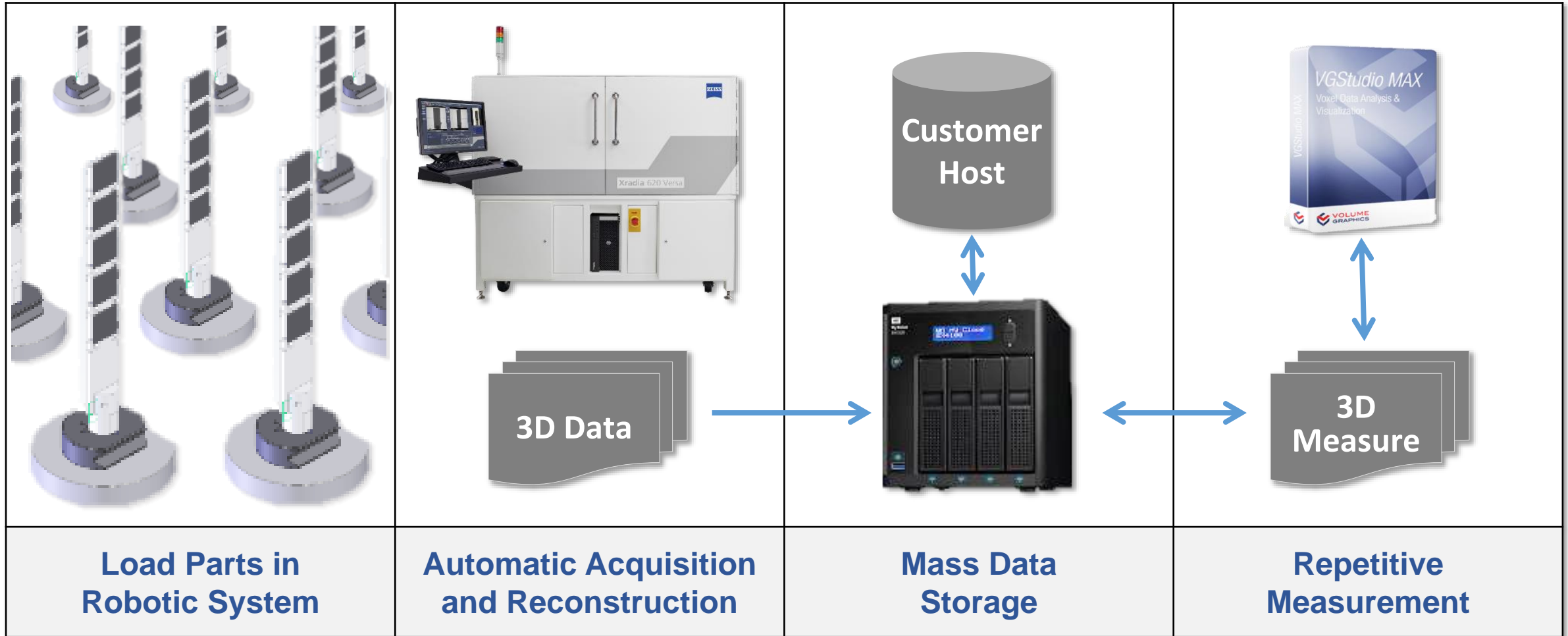


## X-ray Microscopy Measurement

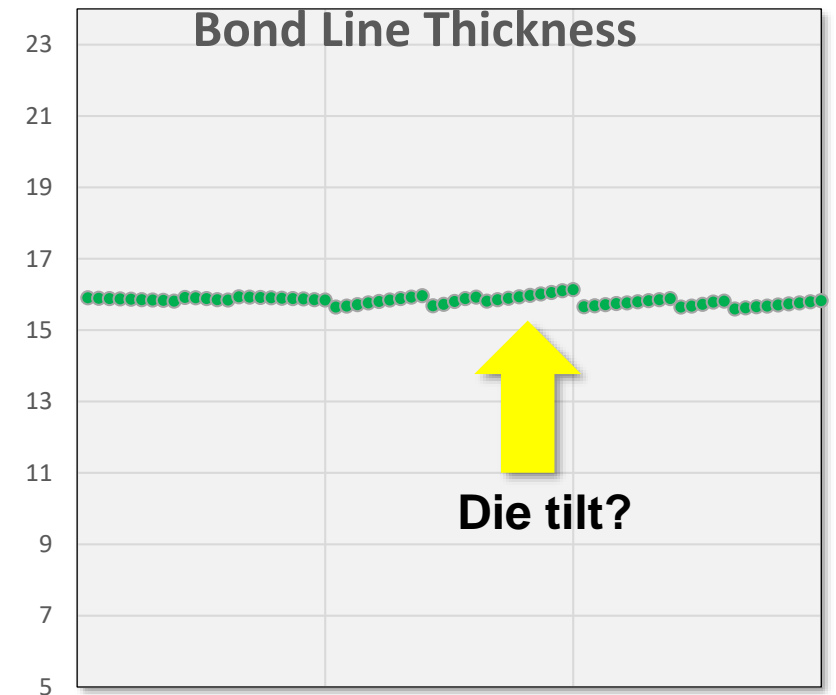
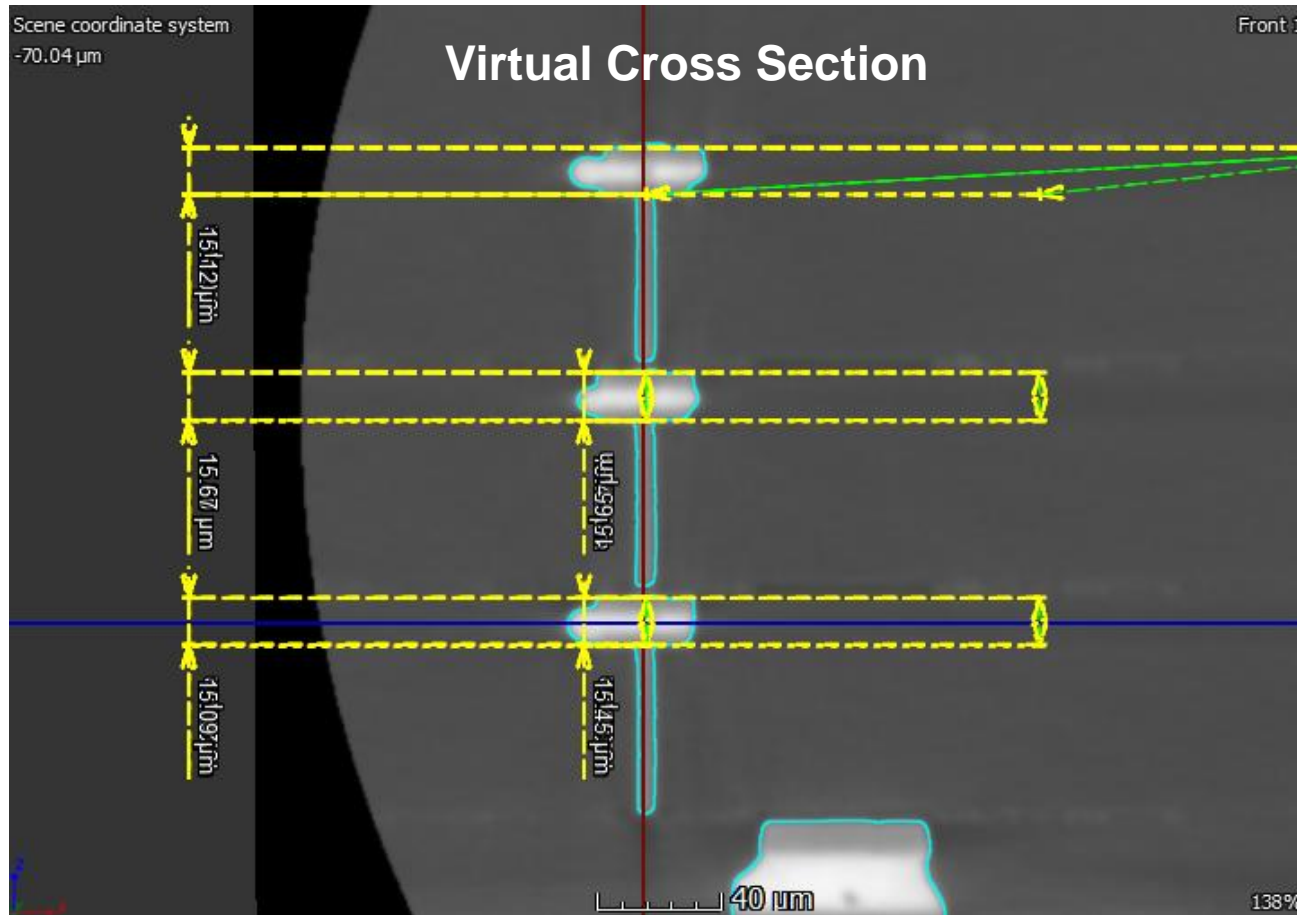


- High-resolution tomography images with automated, repetitive scanning for same package design and location
- Measurement software and ZEISS support enable semi-automated 3D linear and volumetric measurements
- 3D enables many types of metrologies: solder volume, shape, extrusion analysis...

# Versa XRM Measurement Workflow

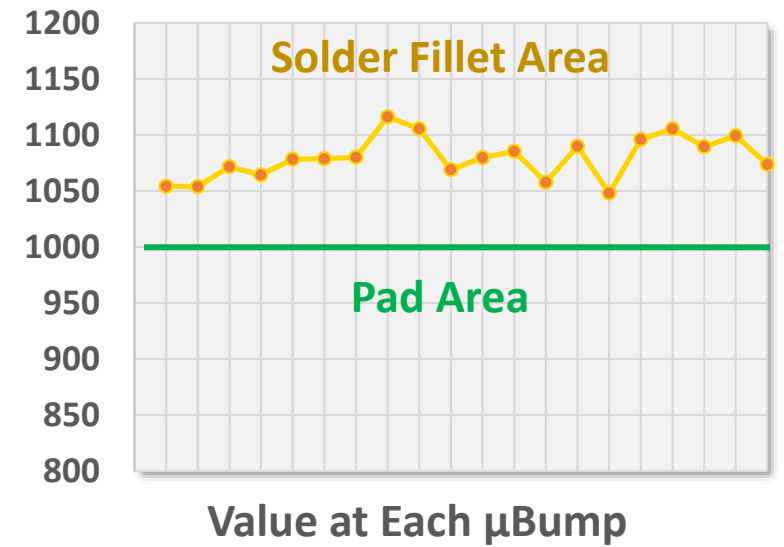
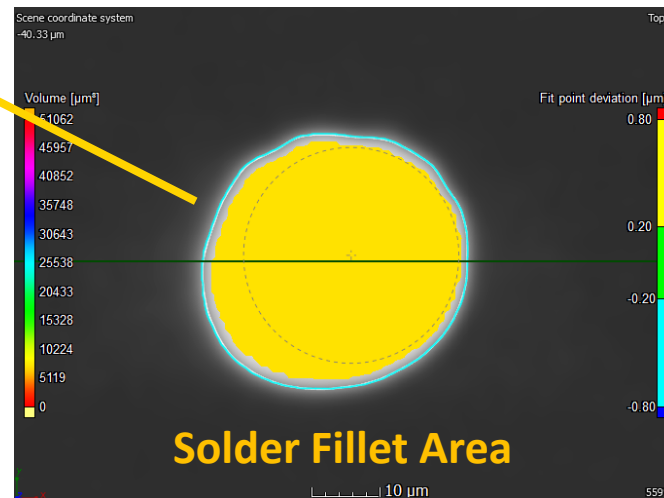
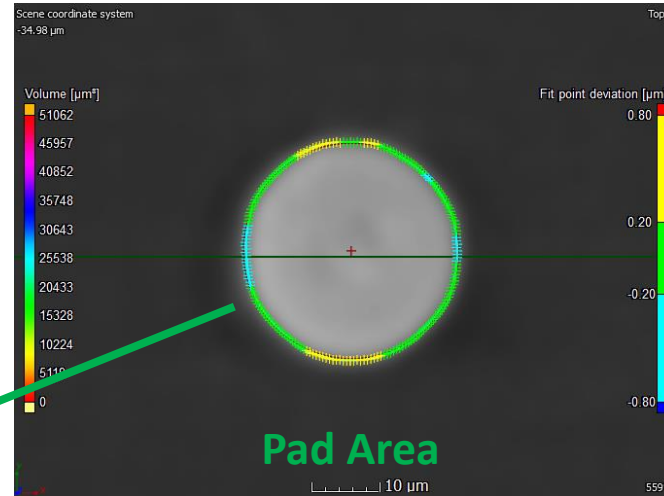
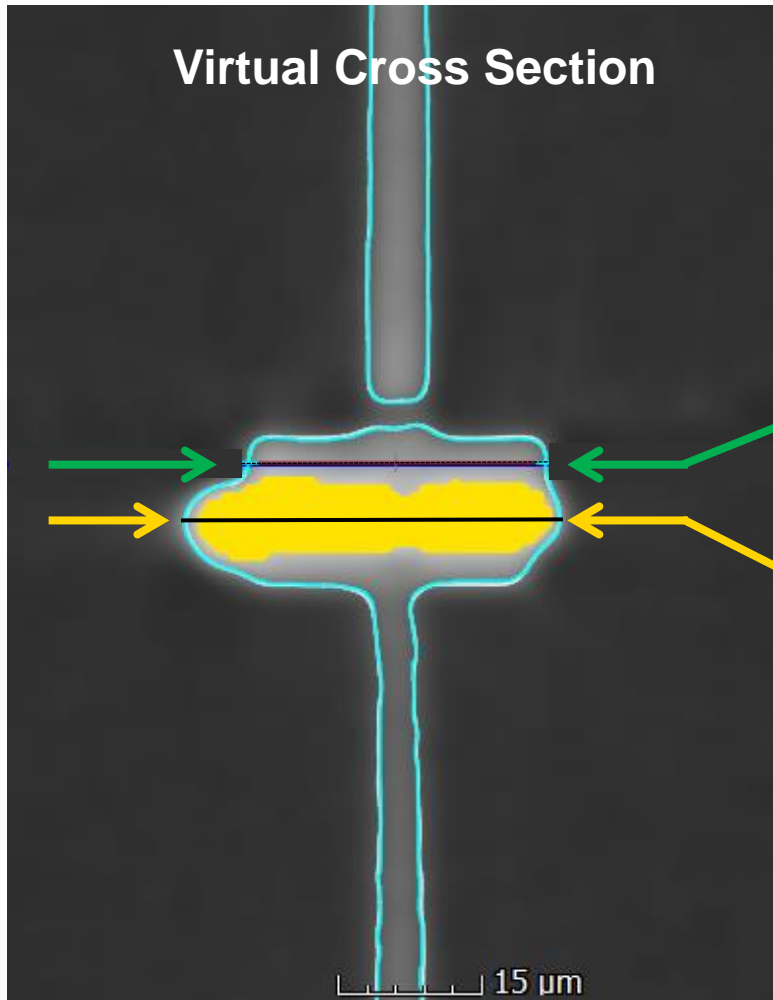


# Case Study #1: $\mu$ Bump TCB Bond Line Thickness

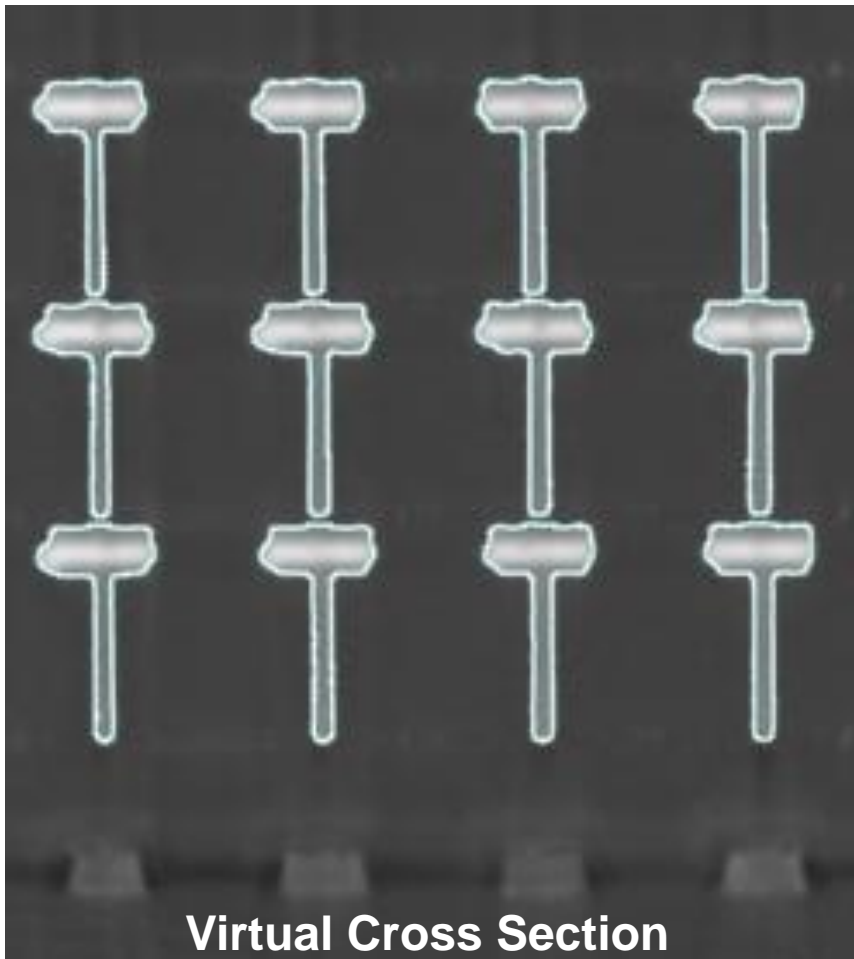


Bond line thickness (BLT) is defined by die-to-die distance

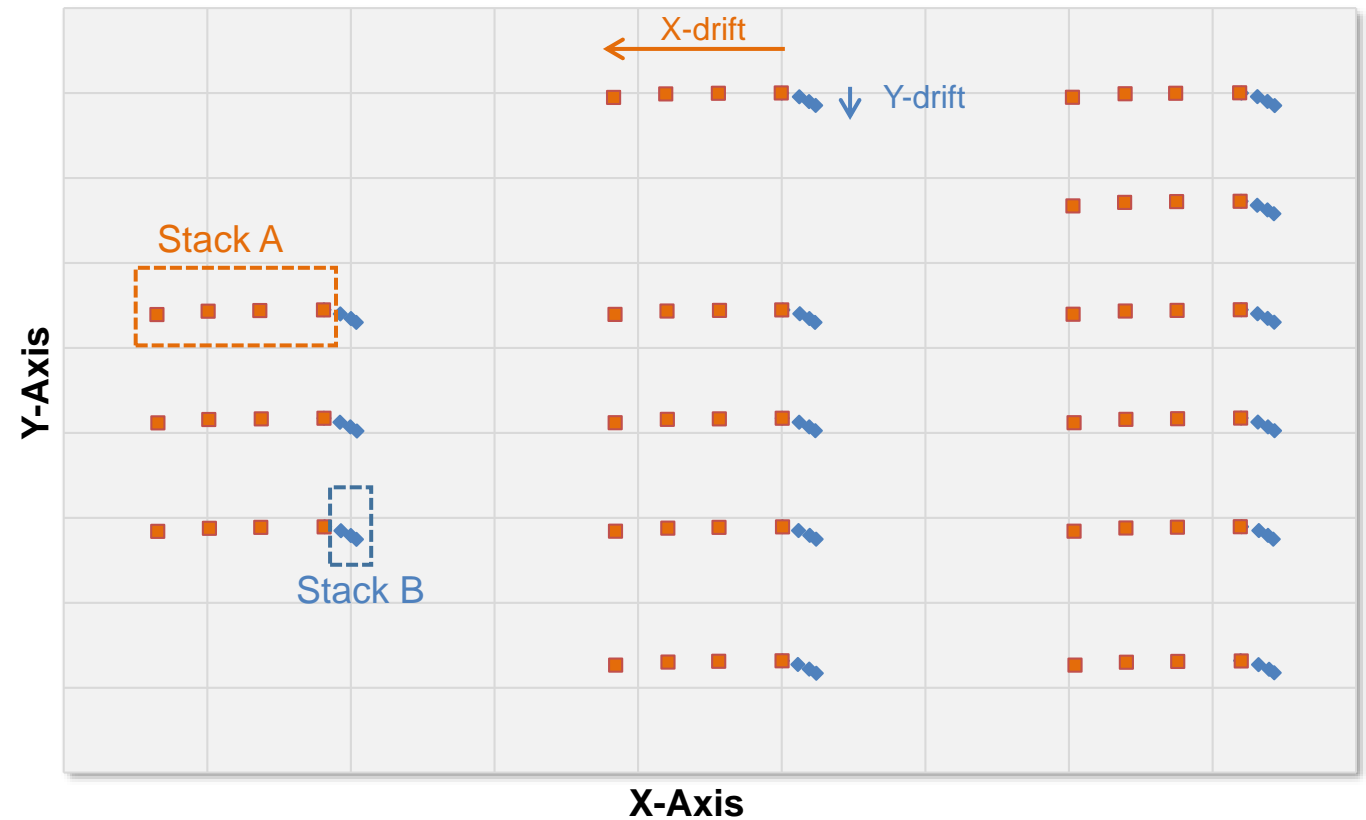
# Case Study #2: $\mu$ Bump Solder Fillet Geometry



# Case Study #3: TSV Array Alignment Analysis



## Top-down Microbump Pad Stack Alignment





# Use of Versa 3D X-ray for Package Measurement

Results in faster, more accurate package development for on-time, on-target product launches by enabling:

- Larger inspection and measurement sample quantities for more robust process optimization
- More accurate, more comprehensive metrology compared to manual cross-section
- Statistically-valid DOEs, process splits and other statistical techniques
- Ability to analyze the same samples both before and after stress testing
- And lower buried costs!





**For more information contact:**

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